

Abstract Submission

An abstract should be written in English on A4 paper within one page. The abstract should have 22.5 mm margins on each side and 30 mm margins top and bottom. All text including title and so on, and a figure (if any) should fit within these margins.

The required parts of the abstract are its title, the list of authors, affiliations with addresses, and the text, in that order. Use of one figure with a caption is encouraged. Please note that we will use black and white; any photo should be high-contrast black and white.

Times and Times New Roman Fonts are the main text fonts; Symbol font may be used for special characters, and Helvetica font for labels within a figure (axis labels, etc.). Please use square brackets [1] for reference citations. Submission of a PDF-file via e-mail is preferred, and a WORD file is also acceptable.

The email address for abstract submission is nss-abst@will.brl.ntt.co.jp

The deadline for Abstract Submission is October 31, 2002.

Registration

All participants including invited speakers need registration and remittance by bank transfer.

REGISTRATION FEE:

Early registration (until October 31, 2002)

15,000 YEN

Late registration

20,000 YEN

The registration fee covers, in addition to access to the workshop, the abstract booklet, welcome party, all coffee breaks, and the workshop banquet.

Please note that the maximum number of participants is limited to 80 only and selection will be made on the basis of "first come, first serve".

Location

The workshop will be held at the International House of Japan, in Tokyo, Japan.

(http://www.i-house.or.jp/ihj_e/index.html)

Program

Sunday, November 24

18:00 - 20:00 Welcome reception at the International House of Japan

Monday - Thursday, November 25 - 28

Scientific presentations, excursion, and social dinner

Friday, November 29

Concluding remarks and "Satellite Workshop" in NTT Basic Research Laboratories

All interested participants are invited to "Satellite Workshop" at 11 am to 7 pm.

Further Information:

Yoshio Watanabe (Workshop Secretary)

NTT Basic Research Laboratories

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Atsugi-shi, Kanagawa 243-0198, Japan

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Conference Committee:

Chair: S. Ushioda - Tohoku University

Vice Chair: G. Salviati - IMEM-CNR Institute

Secretaries: Y. Uehara - Tohoku University

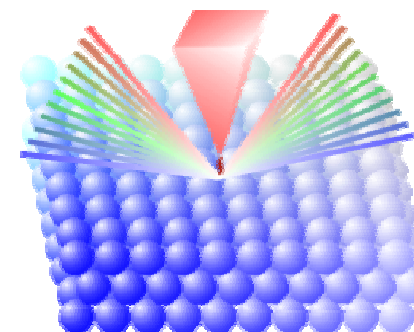
Y. Watanabe - NTT

Treasurer: K. Sakamoto - Tohoku University

2nd International Workshop on Nano-scale Spectroscopy and Nanotechnology

November 25 - 29, 2002

The International House of Japan
Tokyo, Japan



Abstract Deadline : October 31, 2002

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Sponsored by:

Japan Society for the Promotion of Science
Consiglio Nazionale delle Ricerche, Italy

Final Announcement

<http://www.brl.ntt.co.jp/conference/nss2>

Scope

Progress in nanofabrication technology has led to the development of semiconductor nanostructures with characteristic physical properties and potential applications in micro- and optoelectronic devices. To evaluate such nanostructures, different spectroscopic techniques have been developed which can provide a lateral resolution of better than 100 nm. The second International Workshop on Nano-scale Spectroscopy and Nanotechnology provides a forum for the exchange of recent scientific and technical knowledge in this rapidly growing field. Scientists from industry, academia, and government labs are invited to participate. Technical sessions will cover the spectrum from fundamental to applied spectromicroscopic research. Discussion is an important feature of this workshop. Ample time will be available for discussion, both during and between the sessions.

Topics

- Spectromicroscopy with synchrotron radiation (PEEM, Fresnel zone plates, Schwarzschild optics, SXTM)
- Electron microscopy (CL-TEM, CL-SEM, SAM, TEM-EELS, SEM-FA)
- Scanning probe techniques (STS, SNOM, CL-STM, OBIC)
- Nanostructures (quantum dots, quantum wires, nanotubes)
- Nanofabrication technology (nanolithography)

Plenary Speaker

K. Takayanagi, Tokyo Institute of Technology
Quantum Nanowire: Electron Microscopy combined with SPM

Invited Speakers

(alphabetical)

S. F. Alvarado, IBM Zurich Research Laboratory
Nano-scale excitation-spectroscopy and interface studies of semiconducting materials using the STM

R. Berndt, Christian-Albrechts-University of Kiel
STM-based Spectroscopies of Excited Electronic States

M. Bertolo, Sincrotrone Trieste
Photoemission spectromicroscopy studies of superconductor surfaces

R. Cingolani, Università ' di Lecce

M. Colocci, Università ' di Firenze
Light transport in nanostructured materials

S. Frabboni, Università ' di Modena
Application of Energy Filtered Convergent Beam Electron Diffraction to 2-D strain mapping in silicon

S. Heun, Sincrotrone Trieste
AFM local anodic oxidation studied by spectroscopic microscopy

S. Kawata, Graduate School of Osaka University
Tip-enhanced near-field Raman microscopy

T. Kinoshita, University of Tokyo
Photoemission electron microscopic studies at the Photon Factory

M. Kiskinova, Sincrotrone Trieste
Chemical specific imaging and micro-spectroscopy: recent achievements and future projects

T. Koshikawa, Osaka Electro-Communication University
Dynamic observation of nano-structure formation by cathode lens microscopy

K. Miyano, University of Tokyo
Spectroscopy of individual metal nanoparticles
S. Modesti, Università ' di Trieste
Structure and electronic properties of nanostructures in GaAs by cross-sectional scanning tunneling microscopy and spectroscopy

C. Oshima, Waseda University
Coherent Electron Beam

M. Oshima, University of Tokyo
Photoelectron Emission Microscopy for Magnetic Micro/Nanostructures

R. Phaneuf, University of Maryland
Correlation of Time Response and Spectroscopy in STM measurements of Devices

G. Salviati, IMEM-CNR Institute
Depth resolved and power dependent SEM-CL study of GaN/AlN/Si stacked QDs

T. Sekiguchi, National Institute for Materials Science
Characterization of widegap semiconductors and their nanostructures by cathodoluminescence/EBIC

S. Suzuki, NTT Basic Research Laboratories
Photoemission spectromicroscopy of carbon nanotubes

Y. Takiguchi, Hamamatsu Photonics K.K.
Advanced photonics for nano-technology

Y. Tanishiro, Tokyo Institute of Technology
Energy-filtered Reflection Electron Microscopy, Diffraction and Interferometry: Surface plasmon excitation and coherence

Y. Uehara, Tohoku University
Electromagnetic enhancement effect in scanning tunneling microscope light emission from GaAs

N. Ueno, Chiba University
Combined PEEM and MEEM study of organic/metal interfaces

N. Yamamoto, Tokyo Institute of Technology
Optical Properties of Nano-structures in Semiconductors studied by TEM-CL Technique